Prof. Sangsul Lee

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Sangsul is the head of the EUV Metrology and Inspection Group at PAL-EUV in the Pohang Accelerator Laboratory, as well as an affiliated professor of semiconductor engineering at POSTECH.

His research interests cover EUV Lithography, Metrology, and Inspection techniques for semiconductors, as well as In-situ analysis and nanoscale imaging based on synchrotron technology.

From 2020 to 2023, he led the construction project of the EUV Metrology and Inspection beamline at PAL. Before joining PAL-POSTECH, Sangsul worked as a postdoctoral fellow scientist at the Paul Scherrer Institute in Switzerland from 2012 to 2015. During this time, he was responsible for a new beamline construction project aimed at investigating EUV mask metrology technology at the Swiss Light Source.

Sangsul holds a Ph.D. degree in Material Science and Engineering from Hanyang University, Korea, and he earned his master's and bachelor’s degrees in Material Science and Engineering from the same institution. He has authored or co-authored 71 papers in international scientific journals.

His research interests span a broad spectrum within the semiconductor field, with a specific focus on EUV lithography, metrology, and inspection techniques. His expertise also extends to synchrotron-based research, where he has spearheaded breakthroughs in in-situ analysis and nanoscale imaging methodologies.